

**Amendments to the Specification:**

Please replace the paragraph beginning at page 8, line 32, with the following rewritten paragraph:

FIGURES 22A-E ~~22A-F~~ are representations of a series of masks (hatched area) for the manufacture of an enucleation MEMS device.

Please replace the paragraph beginning at page 68, line 12, with the following rewritten paragraph:

Figures 22A-E ~~22A-F~~ show a series of masks and etches that give rise to an individual MEMS device of an enucleation MEMS array. In Figure 22A a first mask 160, is deposited on the surface of a wafer such that a square shape is inscribed 161. The first mask is etched and a well 162 is formed. A second mask 163 is deposited to begin formation of the enucleation penetration member 164. The second mask 163 is etched a third mask 165 is deposited and etched, a fourth mask is deposited and etched, and a fifth mask 167 protects formed enucleation penetration member and allows a central square to be etched such that an enucleation pit 168 is formed. Figure 22E ~~22F~~ illustrates a side-view of the cell well 162 showing the enucleation pit 170, and the enucleation penetration member 169.